

FORM PTO-1449  
(Modified)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
**06381P USA**

SERIAL NO.

**10/624 357****INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**  
(Use several sheets if necessary)

APPLICANT

**Aaron Scott Lukas, et al.**

(37 CFR 1.98(b))

FILING DATE

**7/21/03**

GROUP

**2813****U.S. PATENT DOCUMENTS**

EXAM- INER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
NB		4	6	0	3	1	6	8	7/29/1986	S. Sasaki, et al.	522	18	2/19/1985
NB		5	6	0	9	9	2	5	3/11/1997	R. C. Camilletti, et al.	427	503	12/4/1995
NB		5	9	7	0	3	8	4	10/19/1999	S. Yamazaki, et al.	438	795	8/2/1995
NB		6	0	1	7	8	0	6	1/25/2000	K. C. Harvey	438	475	7/28/1998
NB		6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
NB		6	1	6	8	9	8	0	1/2/2001	S. Yamazaki, et al.	438	162	9/26/1996
NB		6	2	8	4	0	5	0	9/4/2001	J. Shi, et al.	118	715	5/18/1998
NB	01	0	0	3	8	9	1	9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
NB	02	0	1	0	2	4	1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
NB	02	0	1	0	6	5	0	0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001
NB	02	0	1	4	2	5	8	5	10/3/2002	R. P. Mandal	438	633	3/4/2002
NB	03	0	0	3	2	3	0	0	2/13/2003	C. Waldfried, et al.	438	725	5/14/2001
NB	03	0	0	5	4	1	1	5	3/20/2003	R. Albano, et al.	427	487	9/14/2001

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
NB	WO	9	7	0	0	5	3	5		World			X	
NB	WO	02	0	6	5	5	3	4		World			X	

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

NB		E. G. Parada, et al., "Improvement of Silicon Oxide Film Properties by Ultraviolet Excimer Lamp Annealing," Applied Surface Science 86, pp. 294-298 (1995).
NB		A. Guo, et al., "Highly Active Visible-Light Photocatalysts for Curing a Ceramic Precursor," Chem Mater. 10, pp. 531-536 (1998).
NB		T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films," Chem. Mater. 12, pp. 3879-3884 (2000).
NB		M. Brinkmann, et al., "Room-Temperature Synthesis of a-SiO <sub>2</sub> Thin Films by UV-Assisted Ozonolysis of a Polymer Precursor," Chem. Mater. 13, pp. 967-972 (2001).
NB		A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesoporous Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light," Chem. Mater. 12, pp. 3842-3847 (2000).
NB		M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes," Chem. Mater. 12, pp. 1591-1596 (2000).
NB		Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
NB		C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER

**Nema Berezny**

DATE CONSIDERED

**11-30-04**

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



PTO/SB/08A (08-03)  
Approved for use through 07/31/2008. OMB 0651-0031  
U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

<b>Substitute for form 1449/PTO</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> <i>(Use as many sheets as necessary)</i>				<b>Complete If Known</b>	
				Application Number	10/624,357
				Filing Date	July 21, 2003
				First Named Inventor	Aaron Scott Lukas, et al.
				Art Unit	2813
				Examiner Name	Berezny, Nema O.
Sheet	1	of	1	Attorney Docket Number	06381P USA

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
DS		US- 5,935,646	08-10-1999	Raman, et al.	
		US- 6,231,989	05-15-2001	Chung, et al.	
		US- 6,426,236	<del>07-30-2020</del>	Ishizaka, et al.	7/2002
		US- 6,472,076	10-29-2002	Hacker	
		US- 2002/0132496	09-19-2002	Ball, et al.	
		US- 2003/0003288	01-02-2003	Nakata, et al.	
		US- 2003/0087042	05-08-2003	Murakami, et al.	
		US- 2003/0162034	08-28-2003	O'Neill, et al.	
		US- 2003/0198742	10-23-2003	Vrtis, et al.	
		US- 2003/0232137	12-18-2003	Vrtis, et al.	
		US- 2004/0096593	05-20-2004	Lukas, et al.	
		US- 2004/0096672	05-20-2004	Lukas, et al.	
		US-			
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup> (if known)				

Examiner Signature	DS	Date Considered	11/4/06
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